35. Visible Light Induced Water Cleavage in CdS Dispersions Loaded with Pt and RuO₂, Hole Scavenging by RuO₂

by Kuppuswamy Kalyanasundaram, Enrico Borgarello and Michael Grätzel

Institut de Chimie Physique, Ecole Polytechnique Fédérale, CH-1015 Lausanne

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Summary

Illumination of aqueous CdS dispersions loaded with Pt and RuO_2 by visible light produces hydrogen and oxygen in stoichiometric proportion. No degradation of the photocatalyst is noted after 60 h of irradiation time. The RuO_2 deposit on the particle surface greatly accelerates the transfer of holes from the semiconductor valence band to the aqueous solution thus inhibiting photocorrosion.

Cadmium sulfide is a semiconductor¹) characterized by a band gap of 2.4 eV and a position of the valence and conduction band edge around +1.5 and -0.9 V respectively (vs. NHE at pH 7). These properties would make it ideally suited as a photocatalyst for the cleavage of water by visible light (2.4 eV = 517 nm). However, a serious problem associated with the use of this material in light energy conversion devices is its inherent instability under illumination. Holes produced in the valence band migrate to the surface where rapid oxidation of sulfide ions to sulfur occurs:

$$\mathbf{S}^{2-} + 2 \ h^+ \to \mathbf{S}.\tag{1}$$

This photocorrosion process may be prevented [2] by the addition to the solution of a reducing agent such as $Fe(CN)_{6}^{4-}$ or polysulfide ions, acting as a hole scavenger in competition to reaction (1). Unfortunately, in order to be effective the hole ejection from the semiconductor into the solution requires a large driving force and hence uses up a significant fraction of the absorbed photon energy.

Previously [3-5] we reported on the light induced water cleavage in colloidal TiO_2 dispersions where the semiconductor particles were loaded with ultrafine deposits of both Pt and RuO₂. It was shown that the presence of RuO₂ drastically increases the quantum yield of H₂- and O₂-formation under band gap irradiation²). These results indicate that holes in the valence band of TiO_2 can be trapped efficiently by the RuO₂-catalyst which subsequently intervenes as a mediator in

¹) The literature of photoelectrochemical processes on single-crystal semiconductors has been reviewed, e.g. see [1].

²) Kawai & Sakata have found a similar catalytic effect of RuO₂ in the light induced oxidation of organic compounds in mechanically mixed TiO₂/RuO₂ dispersions, *e.g.* see [6].

the water oxidation process. We reasoned therefore that ultrafine RuO_2 -deposits may function as hole scavengers also on other semiconductor materials such as CdS. Such a process would inhibit the photocorrosion (equ. 1) and instead afford oxygen evolution from water. Experimental evidence supporting this concept is given in the present paper which illustrates for the first time water cleavage through illumination of low band gap semiconductors.

The photocatalyst employed consists of CdS particles loaded with both Pt and RuO₂ and was prepared in the following way: a dispersion of 25 mg of CdS (*Fluka*, 99.999%) in 25 ml water was achieved by sonication. An aqueous solution of RuO₄ was added and the mixture stirred for ca. 30 min in day light. Spontaneous RuO₄ decomposition takes place³) yielding an ultrafine RuO₂

$$RuO_4 \rightarrow RuO_2 + O_2 \tag{2}$$

deposit on the CdS particles. The final concentration of RuO_2 was 8 mg/l. The loading with Pt was carried out by photoplatinization: 3 mg of H₂PtCl₆ were added to a solution containing 25 mg of CdS/RuO₂ and 0.5 ml formaldehyde (0.5 M stock solution in methanol/water 2:3). The concentration of formaldehyde was 10^{-2} M. After deaeration with N₂ the dispersion was illuminated for 30 min by a 450-W Xe-lamp through a 320 nm cut-off-filter. This time suffices for quantitative reduction of the Pt-ions by conduction band electrons (the holes created in the valence band are used to oxidize formaldehyde). The excess formaldehyde, methanol and water were then removed under vacuum at 30°. The dried powder had a loading of 40 mg Pt and 8 mg RuO₂/g CdS. Samples of 25 ml solution containing 25 mg catalyst were illuminated in a 35 ml flask through a 400 nm cut-off-filter and a 15 cm water cell to eliminate UV. and IR. radiation. A 450-W Xe-lamp was used as the light source. The gas evolved under illumination was analyzed by gas chromatography. A *Gow Mac* system,





³) The preparation of colloidal RuO₂ has been described in [7].

carbosieve column (35°) and N₂ (for H₂) or He (for O₂) carrier gas was employed. All samples were deaerated prior to illumination by flushing with nitrogen. When oxygen production had to be examined the solutions were saturated with helium.

Results are presented in *Figure 1* where the volume of hydrogen evolved is plotted as a function of irradiation time. After a short induction period the H₂-evolution rate establishes itself at 1.4×10^{-2} ml/h over at least 60 h of irradiation. No rate decrease was observed. A total of 0.8 ml of H₂ was produced after 60 h of irradiation. Oxygen is formed in stoichiometric proportion. The initial pH of the solution was 6.2 and did not change during the photoreaction in buffer free solution. Any significant contribution of photocorrosion (equ. 1) to the overall process would lead to an increase in pH since proton consumption associated with hydrogen formation would not be compensated by H⁺-production resulting from water oxidation⁴).

A series of blank experiments established that the CdS particles are only photoactive in the presence of both the Pt and RuO_2 catalyst. If Pt is omitted no water cleavage is observed. Similarly the system fails to operate if CdS loaded alone with Pt is illuminated. Here rapid photodegradation of the particles and concommitant formation of sulfur is observed. Undoped CdS particles exhibit no photoactivity.

Furthermore, it was noted that the amount of RuO_2 deposited on the CdS particle strongly influenced the H₂ evolution rate. Thus if the concentration of the former is 16 instead of 8 mg/l the quantum yield is increased by a factor of 1.5.

A plausible mechanism for the intervention of the CdS particles in the water cleavage process is illustrated in *Figure 2*. Electrons and holes are initially produced through band gap excitation. The former migrate to Pt-sites where H_2 production from water occurs. The holes on the other hand are trapped by RuO_2 on the surface and subsequently used to produce oxygen from water. As a driving force of *ca.* 600 mV is available, the water oxidation on RuO_2 will be extremely



Fig. 2. Schematic illustration of photoinduced water splitting on CdS particles loaded with Pt and RuO_2

⁴) Inhibition of photocorrosion by RuO_2 was also established by polarographic analysis which showed no increase in Cd^{2+} -concentration after 60 h irradiation time.





fast [8] and hence can compete with surface corrosion via reaction 1. Thus the ultrafine RuO_2 deposit on the CdS surface promotes the transfer of holes from the valence band across the interface to the aqueous solution.

This model was further tested by performing experiments with EDTA-containing solutions; EDTA serves as a sacrificial donor which is irreversibly oxidized during the photoreaction. Results are displayed in *Figure 3*. At first we irradiated CdS particles which were loaded only by Pt. In agreement with the results obtained by *Darwent & Porter⁵*) we find efficient H₂-production. The rate is about 100 times greater than that observed in the absence of EDTA. A striking increase of the H₂-output is observed if RuO₂ is co-deposited with Pt on the CdS particle. The rate is more than doubled and amounts here to 3.6 ml/h. Apparently the role of RuO₂ in this system is to enhance the transfer of holes from the CdS to the EDTA in the electrolyte. This increases the quantum yield of H₂-production at the expense of photocorrosion.

In conclusion we have illustrated the decisive influence of RuO_2 on valence band processes in illuminated CdS particles. This catalyst, when deposited in ultrafine form, promotes oxidation of water or other electron donors at the CdSelectrolyte interface and thus diminishes the rate of photocorrosion. The quantum efficiency of the water cleavage process obtained so far is about 60 times smaller than that achieved with colloidal TiO₂ dispersions [3-5] loaded with RuO₂ and Pt.

⁵) We thank these authors for communicating us their results prior to publication. Photochemical reactions on CdS powders have been widely investigated, *e.g.* see [9].

However the system may be improved significantly by further optimization. More importantly, the hole stabilizing ability of RuO_2 may be exploited in a photoelectrochemical device consisting of n-type single crystal CdS connected to a Pt counter electrode. Oxygen would be produced at the illuminated CdS surface covered with an ultra-thin layer of RuO_2 while H_2 would be evolved at the Pt counter electrode. Work in this direction is now in progress.

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